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LIST OF	REFE	RENCES CITED BY AP	PPLICANT	APPLICANT	_				
2.3	1100	\Li\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\	FUGAT	Geoffrey J. DAVIES, et al.					
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U.S. PATENT DOCUMENTS									
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS		ILING DATE PPROPRIATE	
اللا	AA	4,551,316	11/85	lizuka	1	I			
	AB	5,151,107	09/92	Cho et al.					
	AC	6,270,548	08/01	Campbell et al.					
A	AD	6,576,211	06/03	Davies et al.	1	I			
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OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)									
*	AW	Hongchang YU et al; "Sintering of Ultrafine Diamond Particles Under High Temperature and High Pressure"; Diamond and Related Materials, Vol. 3, No. 3, pp. 222-226; 02/01/94							
	AX	Shi Ming HONG et al.; "Diamond Formation from a System of SiC and a Metal"; Diamond and Related Materials, Vol. 2, pp. 508-511; 1993							
<del></del>		Jae-Kap LEE et al.; "Effect of the Bucyancy Force on Diamond Formation During Synthesis Under a High Pressure"; Vol. 2,							
	AY	pp. 469-499; 03/01/93							
A	AZ	A.V. ANDREYEV et al.; "Diamond Formation and Wettability in a Mg-Cu-C System Under High Pressure and High Temperature"; Vol. 6, No. 1, pp. 28-32; 01/1997  Additional References sheet(s) attached							
Examiner Date Considered \$700								20	
*Examiner: In	itial if re	aference is considered,	whether or not	t citation is in conformance with MPEP 60	l		citation i	if not in	
conformance and not considered. Include copy of this form with next communication to applicant.									